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IN THE UNITED STATES DESIGNATED/ELECTED OFFICE (DO/EO/US)

In re Application of

BERND LOCHEL ET AL

U.S. Serial No.

Filed: November 9, 2000

METHOD OF AND APPARATUS FOR
DRYING PHOTO RESIST LAYERS

International Application No. PCT/DE99/01485
International Filing Date: May 12, 1999

Alexandria, Virginia
November 9, 2000

United States Designated/Elected Office (DO/EO/US)
Washington, D.C. 20231

INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR §1.97

Dear Sirs:

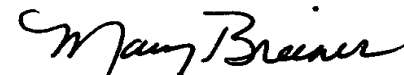
Applicant is submitting herewith a copy of the
following patent document:

European Patent Application 0 509 962 A1

The above listed documents are set forth
together with the applicants and issue or publication
date thereof in the attached PTO Form 1449.

Respectfully submitted,
BERND LOCHEL

By



Mary J. Breiner, Attorney
Registration No. 33,161
115 North Henry Street
P.O. Box 19290
Alexandria, Virginia 22320-0290

Telephone: (703) 684-6885

Attachments - PTO Form 1449 w/1 Document

